

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("20060057240").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/09/21 21:09
S2	3380	((118/720,721,504,505) or (156/345.3) or (204/298.11)).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/21 21:16
S3	48	S2 and vector	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 21:16
S5	41	S3 and (@ad<="20030919" or @rlad<="20030919")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 22:55
S6	7	S3 not S5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 21:45
S7	15	S3 and mask	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 21:57
S9	2	("2433635").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/09/21 22:21
S10	596	mask\$3 same (move or movable or moving or moved) same vector	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:05

## EAST Search History

S11	393	S10 and (@ad<="20030919" or @rlad<="20030919")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 22:24
S12	158	S11 and (deposit\$3 or coat\$3 or sputter\$3 or substrate or wafer or workpiece or (work piece) or (object adj2 treated))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:06
S13	235	S11 not S12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 22:52
S14	3	single action edge	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 22:54
S15	124	mask\$3 and (ternary with thin film)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 22:55
S16	110	S15 and (@ad<="20030919" or @rlad<="20030919")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:04
S17	1	S16 and vector	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:05

## EAST Search History

S20	3892	(mask\$3 same vector) and (move or movable or moving or moved)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:09
S21	1038	(S20 and (deposit\$3 or coat\$3 or sputter\$3 or substrate or wafer or workpiece or (work piece) or (object adj2 treated)) and (@ad<="20030919" or @rlad<="20030919")) not (S5 or S10)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:24
S22	161	S21 not (optical or ink or print\$4 or dna)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:13
S23	19784	mask\$3 and (move or movable or moving or moved) and vector and (angle or degree)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:23
S24	196	(S23 and (deposit\$3 or coat\$3 or sputter\$3 or substrate or wafer or workpiece or (work piece) or (object adj2 treated)) and (@ad<="20030919" or @rlad<="20030919")) not (S5 or S10 or S22 or optical or ink or print\$4 or dna or bus or (signal processing) or image or (cathode ray tube) or CRT or data)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2007/09/21 23:35